

A B S T R A C T

A HEATER LINER FOR A PLASMA ETCHING REACTOR, AND AN
ETCHING METHOD USING THE LINER

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In a reactor of the invention, the reaction chamber
(1) is defined by a leakproof wall (2) protected by a
heater liner (14). The heater liner (14) is raised to a
temperature higher than the condensation temperature of
10 the polymers that are generated during the passivation
step of an alternating plasma etching method so as to
avoid depositing polymer on the leakproof wall (2) of the
reaction chamber (1) or on the heater liner (14) itself.
As a result, etching speed is kept constant.

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35 Translation of the title and the abstract as they were when originally filed by the
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